

WHAT IS CLAIMED IS:

Sub A1 → 1. A method of manufacturing a liquid crystal display apparatus having, on one of a pair of substrates disposed so as to be opposed with a liquid crystal layer therebetween, reflecting means for reflecting incident light from the other substrate, comprising the steps of:

applying a photosensitive resin on one of the substrate;
forming asperities in a first region of the applied photosensitive resin film by exposing the first region with various integrals of exposure amount so that the photosensitive resin in the first region is left in different film thicknesses, and forming in a second region of the applied photosensitive resin film a concave portion so that the photosensitive resin in the second region is left in a thickness smaller than those of the first region by exposing the second region with an integral of exposure amount different from those for the first region;

developing the exposed photosensitive resin;
heat-treating the developed photosensitive resin; and
forming a reflecting film on the heat-treated photosensitive resin.

2. The method of manufacturing a liquid crystal display apparatus of claim 1, wherein a reflecting electrode comprising the reflecting film is formed in the first region of the photosensitive resin and that the reflecting electrode is

connected to wiring formed in a lower layer of the reflecting electrode in the second region of the photosensitive resin.

3. The method of manufacturing a liquid crystal display apparatus of claim 1, wherein a terminal portion is formed in an outside display region on one of the substrates and that the second region of the photosensitive resin is formed in the terminal portion.

4. The method of manufacturing a liquid crystal display apparatus of claim 1, wherein the photosensitive resin is negative, and the step of exposing the photosensitive resin includes a step of exposing the photosensitive resin using a photomask having a light transmitting portion, a light intercepting portion and a semi-light transmitting portion, to form the first region in regions corresponding to the light transmitting portion and semi-light transmitting portion of the photomask, and the second region in a region corresponding to the light intercepting portion of the photomask.

5. The method of manufacturing a liquid crystal display apparatus of claim 1, wherein the photosensitive resin is positive, and the step of exposing the photosensitive resin includes a step of exposing the photosensitive resin using a photomask having a light transmitting portion, a light intercepting portion and a semi-light transmitting portion, to form the first region in regions corresponding to the light intercepting portion and semi-light transmitting portion of the

photomask, and the second region in a region corresponding to the light transmitting portion of the photomask.

6. The method of manufacturing a liquid crystal display apparatus of claim 1, wherein the step of exposing the photosensitive resin includes a step of exposing the photosensitive resin using a first photomask and a step of exposing the photosensitive resin using a second photomask, to form the first region and the second region with the first and second photomasks, respectively.

7. The method of manufacturing a liquid crystal display apparatus of claim 6, wherein the exposure amount at the step of exposing the photosensitive resin using the first photomask and the exposure amount at the step of exposing the photosensitive resin using the second photomask are the same.

8. The method of manufacturing a liquid crystal display apparatus of claim 6, wherein uniform and low-illuminance exposure is performed at the step of exposing the photosensitive resin using the first photomask, while uniform and high-illuminance exposure is performed at the step of exposing the photosensitive resin using the second photomask.

9. The method of manufacturing a liquid crystal display apparatus of claim 8, wherein circular or polygonal regions are irregularly disposed in the first or second photomask and that the total area of the circular or polygonal regions is in a range of from 20% to 40% of the total area of the photomask.

